IN THE CLAIMS

Please amend the claims as follows:

- 1. (Currently Amended) A glazing assembly comprising at least one transparent substrate, especially made of glass, provided with a thin-film multilayer comprising, in the following order starting from the substrate, at least:
- (a) a first dielectric layer comprising a barrier layer acting as a barrier to the diffusion of oxygen and chosen from comprising silicon nitrides;
- (b) a lower stabilizing layer made of at least one metal or metal alloy X selected from the group consisting of titanium, nickel, chromium, niobium, zirconium, tantalum, aluminum or a metal alloy containing at least one of these metals;
- (c) a functional layer having reflection properties in the infrared and/or in the solar radiation, especially a metal layer;
- (d) an upper metal blocking layer made of at least one metal or metal alloy Y selected from the group consisting of titanium, nickel, chromium, niobium, zirconium, tantalum, aluminum or a metal alloy containing at least one of these metals;
- (e) a second dielectric layer comprising a barrier layer acting as a barrier to the diffusion of oxygen and chosen from silicon nitrides; and
- (f) optionally, a protective oxide layer; in which multilayer the metal or alloy X of the lower stabilizing layer is different from the metal or alloy Y of the upper blocking layer.
- 2. (Currently Amended) The glazing assembly as claimed in claim 1, eharacterized in that-wherein the thickness of the dielectric layer (a) and (e), respectively, is at least 5 nm₅ especially between 15 and 70 nm.

Claim 3 (Cancelled).

- 4. (Currently Amended) The glazing assembly as claimed in claim 1, wherein 3, characterized in that_the stabilizing lower metal layer (b) is made of comprises a nickel-chromium alloy.
- 5. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that wherein the thickness of the layer (b) is between 1 and 6 nm.
- 6. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that wherein the layer (c) is a metal layer based on silver, titanium, palladium or gold.
- 7. (Currently Amended) The glazing assembly as claimed in claim 6, characterized in that wherein the layer (c) has a thickness of 6 to 12 nm.

Claim 8 (Currently Amended) The glazing assembly as claimed in claim [[3]] 1, characterized in that wherein the upper metal blocking layer (d) is made of a metal Y chosen from titanium, zirconium, niobium and aluminum.

- 9. (Currently Amended) The glazing assembly as claimed any one of the preceding claims claim 1, characterized in that wherein the thickness of the layer (d) is less than 6 nm.
- 10. (Currently Amended) The glazing assembly as claimed in-one of the preceding claims claim 1, characterized in that wherein the thickness of the layer (b) is greater than that of the

- 11. (Currently Amended) The glazing assembly as claimed in any one of the preceding elaims claim 1, characterized in that wherein at least one (in particular each) of the dielectric coatings layers may comprise further comprises a layer based on one or more metal oxides.
- 12. (Currently Amended) The glazing assembly as claimed in any one of the preceding elaims claim 1, characterized in that which comprises an outer layer (f) based on an oxide of at least one metal chosen from Zn, Al, Ti, Sn, Zr, Nb, W, and Ta.
- 13. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that wherein the multilayer comprises, on the substrate comprises glass, the sequence:
- 14. (Currently Amended) The glazing assembly as claimed in claim 13, characterized in that the multilayer which comprises in the following order starting from the substrate /silicon nitride/nickel-chromium/Ag/titanium/silicon nitride/nickel-chromium/Ag/titanium/silicon nitride/. [[. .]]
- 15. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that which is mounted with another substrate as a double glazing assembly to form a unit and the unit has a light transmission of between 40 and 70%.
- 16. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that which has a selectivity defined by [[the]] a ratio of

[[the]] light transmission to [[the]] solar factor, T_L/SF of between 1.25 and 1.45.

- 17. (Currently Amended) The glazing assembly as claimed in any one of the preceding claims claim 1, characterized in that which has a blue-green color in reflection.
- 18. (Currently Amended) The glazing assembly as claimed in any one of the preceding elaims claim 1, characterized in that the substrate, once it has been provided with the thin-film multilayer, which undergoes a heat treatment at more than 500° C after the multilayer is provided to the substrate, of the bending, toughening or annealing type, especially with an average light transmission change ΔT_L induced by the heat treatment of at most 3%, preferably around 2%, and/or an average change in calorimetric response in reflection induced by the heat treatment ΔE^* of at most 3, especially 2.5.

Claim 19 (Cancelled).

- 20. (Currently Amended) A glazed unit incorporating several glazing assemblies comprising at least two glazing assemblies as claimed in claim 1 any one of claims 1 to 18.
- 21. (Currently Amended) The glazed unit as claimed in the preceding-claim 20, characterized in that it incorporates wherein at least one glazing assembly that has undergone a heat treatment and at least one glazing assembly that has not undergone heat treatment.
- 22. (New) The glazing assembly as claimed in claim 1, wherein the thickness of the dielectric layer (a) and (e), respectively, is between 15 and 70 nm.

23. (New) The glazing assembly as claimed in claim 1, which undergoes a heat treatment at more than 500° C after the multilayer is provided to the substrate-with an average light transmission change ΔT_L induced by the heat treatment of around 2% and/or an average change in calorimetric response in reflection induced by the heat treatment ΔE^* of at most 2.5.